

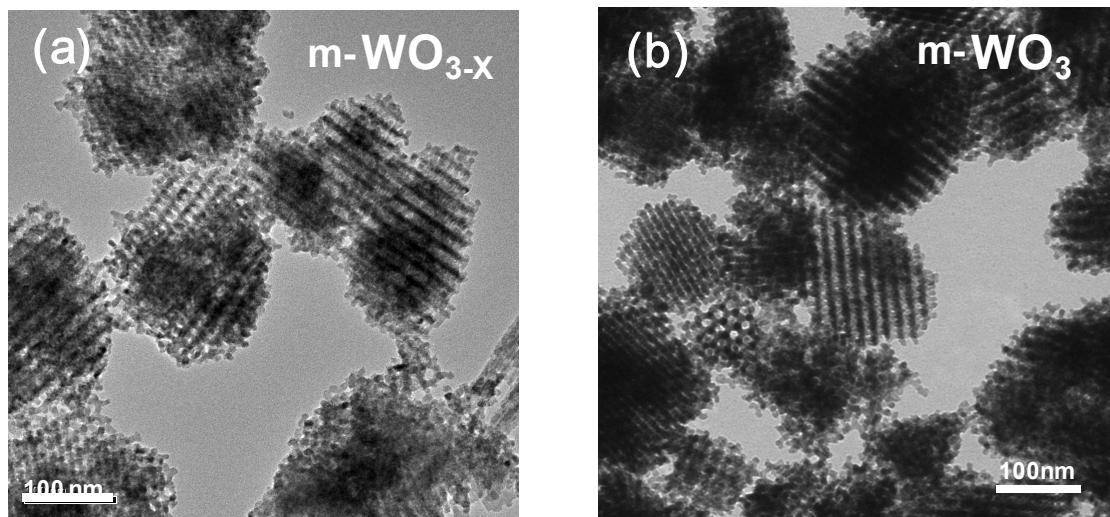
# Development of High-Performance Supercapacitor Electrodes Using Novel Ordered Mesoporous Tungsten Oxide Materials with High Electrical Conductivity

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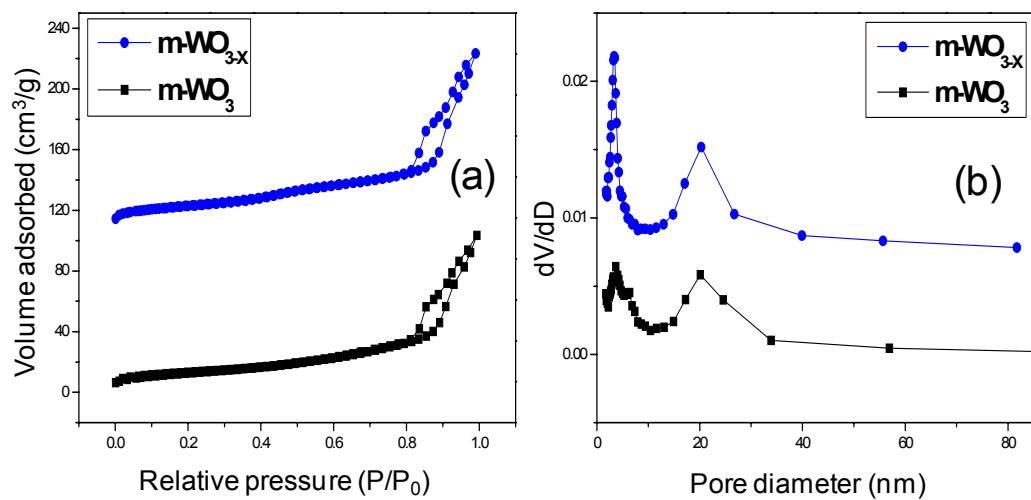
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*Synthesis of m-WO<sub>3-x</sub>, m-WO<sub>3</sub> and b-WO<sub>3</sub>:* Mesoporous silica KIT-6 was used as a hard template and synthesized following the reported procedure.<sup>1</sup> KIT-6 was impregnated with phosphotungstic acid in two steps. In first impregnation stage, 1.2 g of phosphotungstic acid was incorporated into the pores of 0.45 g KIT-6 by impregnation method and calcined at 350 °C under air. In the second impregnation step, 0.6 g of phosphotungstic acid was incorporated into the pores of prepared composite, and calcined at 550 °C under air to obtain WO<sub>3</sub>/KIT-6. HF etching of WO<sub>3</sub>/KIT-6 generated m-WO<sub>3</sub>. To obtain m-WO<sub>3-x</sub>, WO<sub>3</sub>/KIT-6 composite was heat-treated at 600 °C under Ar/H<sub>2</sub> (4 wt%) atmospehre for 4 hours and further stirred with 5 wt% HF solution for the removal of silica.<sup>2</sup> b-WO<sub>3-x</sub> (bulk WO<sub>3-x</sub>) was prepared following the same procedure for m-WO<sub>3-x</sub> except KIT-6 was not used.

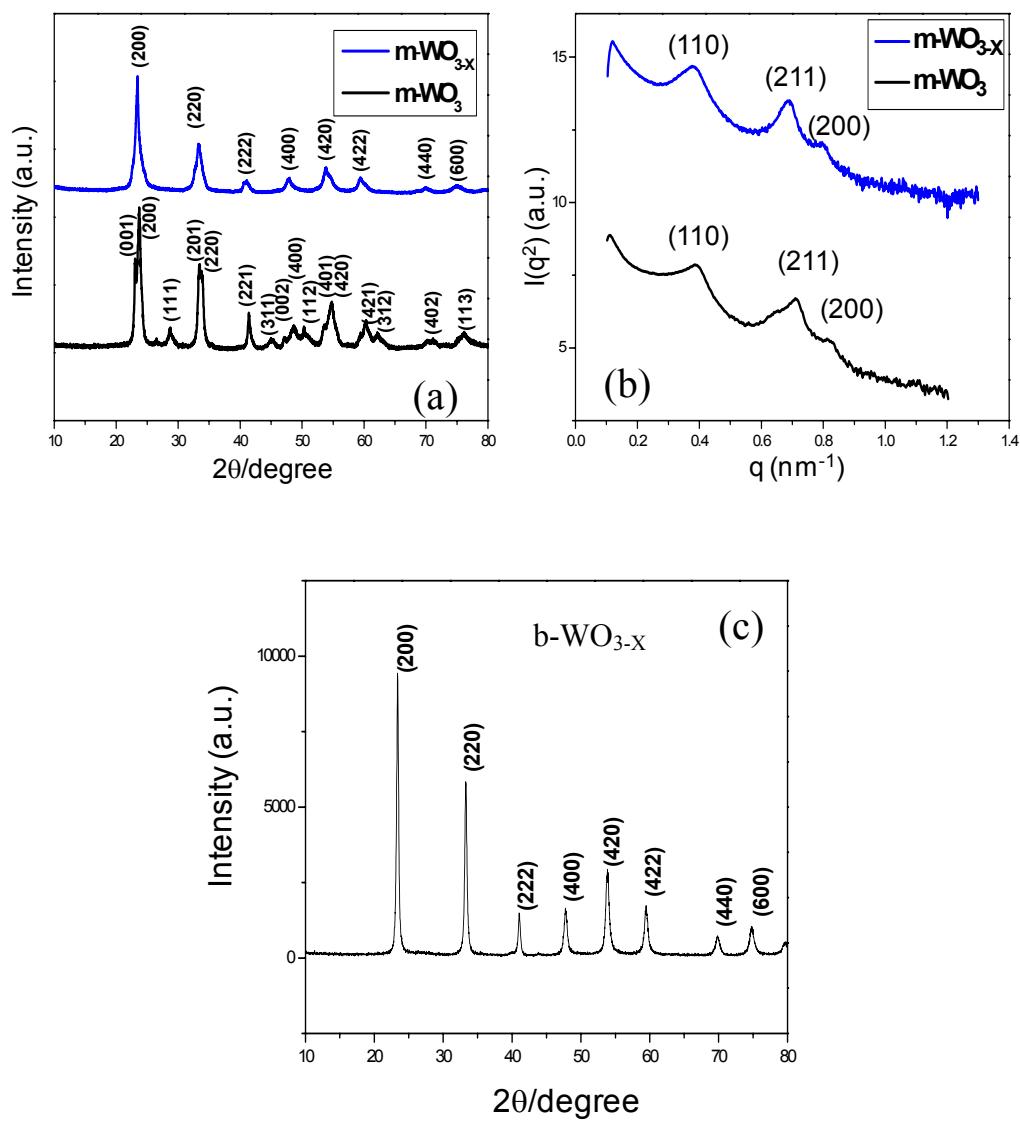


**Figure S1.** TEM images of (a) m-WO<sub>3-x</sub> and (b) m-WO<sub>3</sub>. Both materials were synthesized using KIT-6 hard template and have the same ordered pore structure.



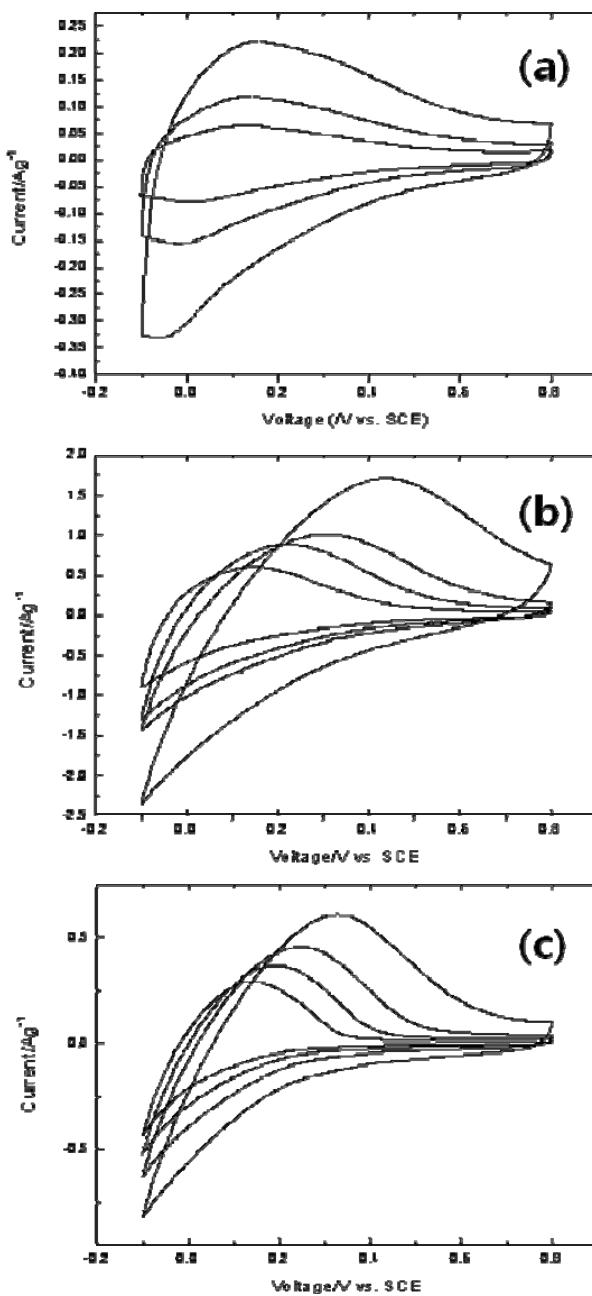
**Figure S2.** (a) Nitrogen adsorption-desorption isotherms of m-WO<sub>3-x</sub> and m-WO<sub>3</sub> (b) Pore size distributions of m-WO<sub>3-x</sub> and m-WO<sub>3</sub> estimated from adsorption branch using BJH (Barett-Joyner-Halenda). The pore structure of m-WO<sub>3</sub> judged by N<sub>2</sub> isotherm and pore size distributions is nearly identical to that of m-WO<sub>3-x</sub>. An N<sub>2</sub> adsorption shows

two distinct jumps at  $\sim 0.5$  P/P<sub>0</sub> and  $\sim 0.9$  P/P<sub>0</sub>, corresponding to uniform 3.5 nm pores and  $\sim 20$  nm pores observed in pore size distributions, respectively.  $\sim 20$  nm sized pores might be produced by filling phosphotungstic acid in either one of two chiral channels and removal of KIT-6 template.<sup>2</sup>

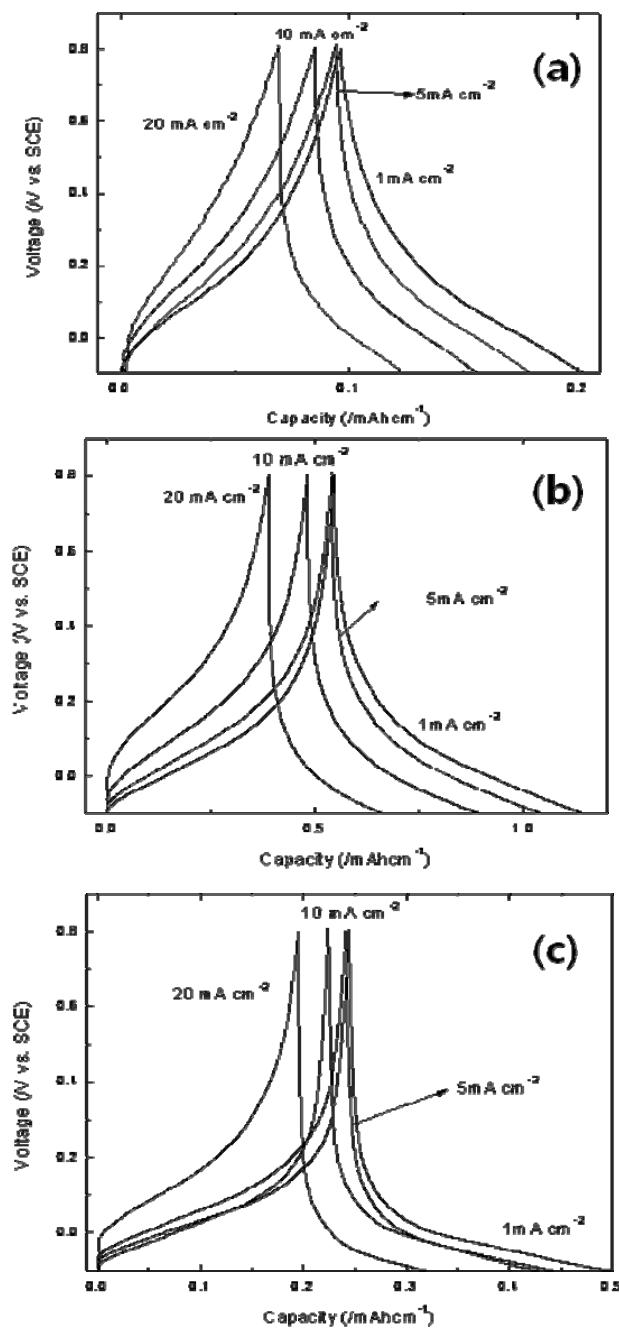


**Figure S3.** (a) XRD patterns of  $m\text{-WO}_{3\text{-}X}$  and  $m\text{-WO}_3$ . Diffraction peaks in  $m\text{-WO}_{3\text{-}X}$

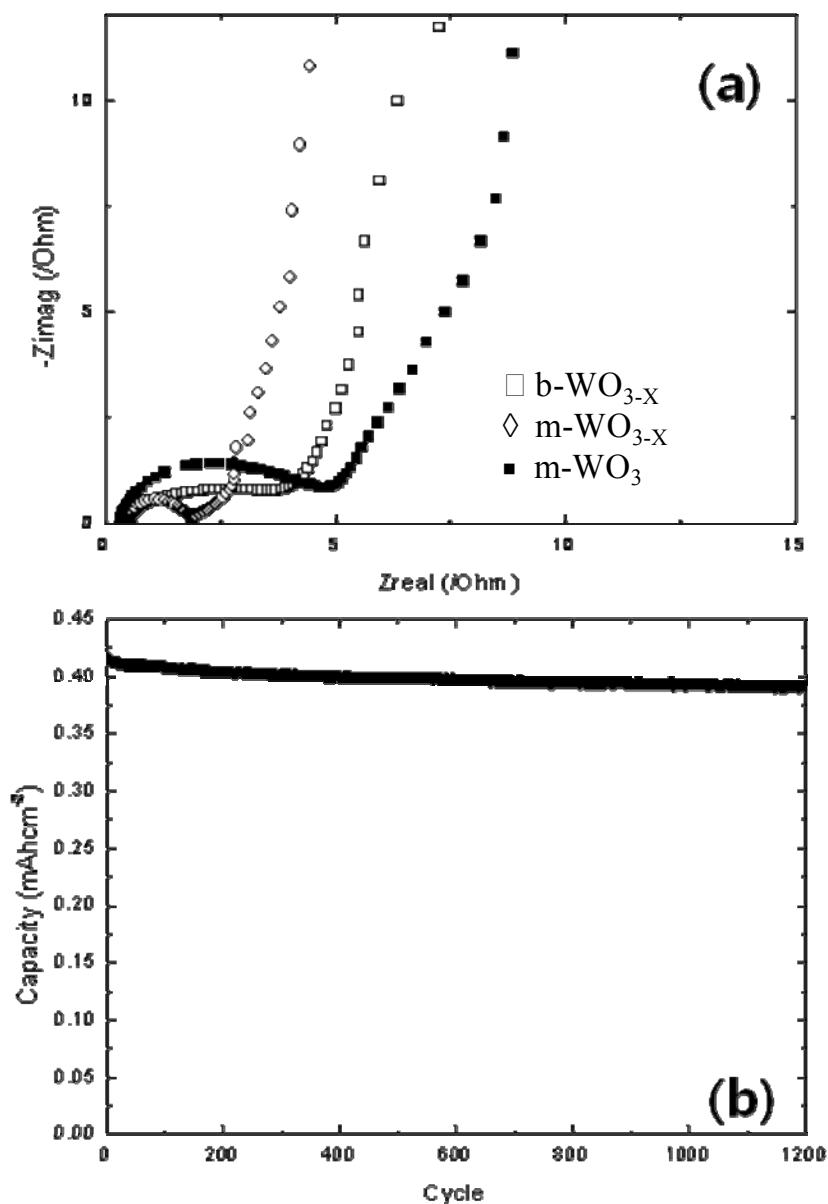
can be indexed to the cubic  $\text{WO}_{3-\text{x}}$  phase (JCDPS:46-1096). The XRD pattern of m- $\text{WO}_3$  is well-matched with tetragonal phase (JCDPS:89-1287) (b) Small angle X-ray scattering (SAXS) patterns of m- $\text{WO}_{3-\text{x}}$  and m- $\text{WO}_3$ . (c) XRD pattern of b- $\text{WO}_{3-\text{x}}$ . Diffraction peaks in b- $\text{WO}_{3-\text{x}}$  can be indexed to the cubic  $\text{WO}_{3-\text{x}}$  phase (JCDPS:46-1096)



**Figure S4.** Cyclic voltamograms with change of scan rate from 5 to 50 mV/s for  $\text{b}-\text{WO}_{3-\text{x}}$  (a),  $\text{m-WO}_{3-\text{x}}$  (b) and  $\text{m-WO}_3$  (c)



**Figure S5.** Galvanostatic charge-discharge patterns with change of applied current from 1 to 20 mA/cm<sup>2</sup> for b-WO<sub>3-X</sub> (a), m-WO<sub>3-X</sub> (b) and m-WO<sub>3</sub> (c)



**Figure S6.** (a) Electrochemical impedance spectra for three tungsten oxide electrodes when 5 mV voltage magnitude from 5 mHz to  $10^5$  Hz at open circuit voltage (OCV). (b) Change of capacity with cycles of m-WO<sub>3-X</sub> electrodes.

## References

1. F. Kleitz, S. H. Choi, R. Ryoo, *Chem. Commun.* 2003, 2136.
2. (a) Shi, Y.; Guo, B.; Corr, S. A.; Shi, Q.; Hu, Y. -S.; Heier, K. R.; Chen, L.; Seshadri, R.; Stucky, G. D. *Nano Lett.* 2009, **9**, 4215. (b) Kang, E.; An, S.; Yoon, S.; Kim, J. K.; Lee, J. *J. Mater. Chem.* 2010, **20**, 7416.